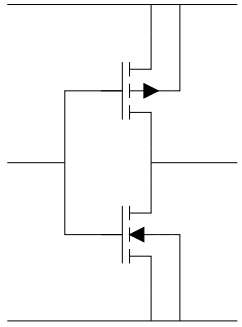
Design Rules

0.5 μm CMOS inverter



N-well

Active Area

P implant

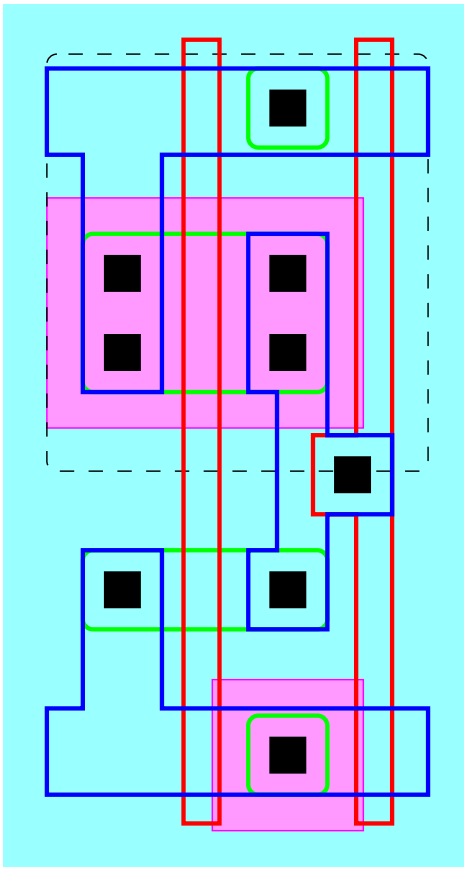
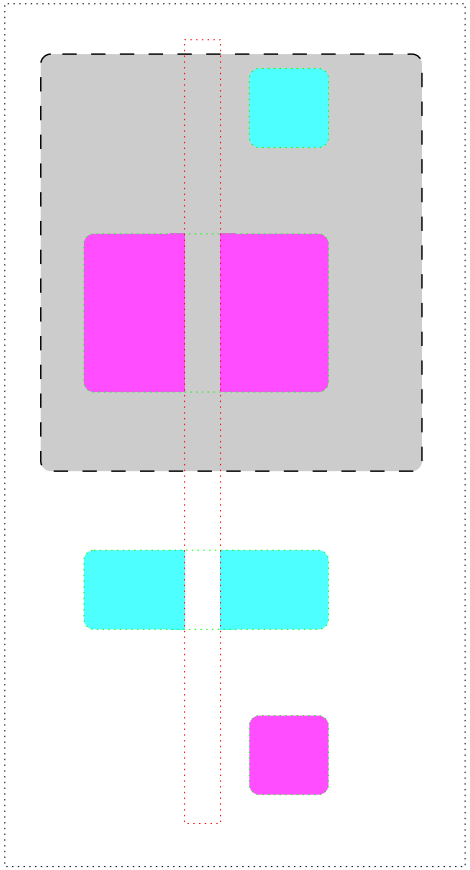
Polysilicon

Contact Window

Metal

N implant = NOT{ P implant }

Masks



Actual Diffusion Areas